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Information Disclosure Statement by Applicant

Applicant: Chen et al.

(Use several sheets if necessary)

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**U.S. Patent Documents**

Init.	Document No.	Date	Name	Class	Subclass	Filing Date
Wu	1 6,154,410	11/28/2000	Cutter et al.	365	225.7	02/05/1997
Wu	2 6,259,130 B1	07/10/2001	Wu	257	314	03/09/1999
Wu	3 6,413,833 B2	07/02/2002	Yamamoto	438	398	01/29/1999
Wu	4 6,440,869 B1	08/27/2002	Tseng	438	734	06/26/2000

**Foreign Documents**

Init.	Document No.	Date	Country	Class	Subclass	Translation	
						Yes	No

**Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)**

Wu	2/95	H. Watanabe et al., "An Advanced Technique for Fabricating Hemispherical-Grained (HSG) Silicon Storage Electrodes", <u>IEEE Transactions On Electron Devices</u> , Vol. 42, NO. 2, pp. 295-300, February 1995.					

Examiner W. J. [Signature] Date Considered 8/28/04

Examiner: Initial if citation considered, whether or not citation is in conference with MPEP 609; Draw line through citation if not conformance and not considered. Include a copy of this form with the next communication to applicant.

